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PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Docket No: Q68554

Tsutomu SHOKI, et al.

Appln. No.: 10/073,874

Group Art Unit: 1756

Confirmation No.: 6741

Examiner: Stephen D. ROSASCO

Filed: February 14, 2002

For: REFLECTION TYPE MASK BLANK FOR EUV EXPOSURE AND REFLECTION  
TYPE MASK FOR EUV EXPOSURE AS WELL AS METHOD OF PRODUCING THE  
MASK

**AMENDMENT UNDER 37 C.F.R. § 1.111**

**MAIL STOP NON-FEE AMENDMENT**

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Sir:

In response to the Office Action dated September 10, 2003, please amend the above-identified application as follows on the accompanying pages.